L Number	Hits	Search Text	DB	Time stamp
1	11875	(pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry	USPAT; US-PGPUB	2004/09/30 15:14
2	3636	((pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry) and ((hydrocarbon CH4 ("CH.sub.4")) and argon and oxygen "O.sub.2")	USPAT; US-PGPUB	2004/09/30 15:12
3	2	((pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry) and ((hydrocarbon CH4 ("CH.sub.4")) near5 argon near5 (oxygen "O.sub.2"))	USPAT; US-PGPUB	2004/09/30 15:08
4	21	((pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry) and ((hydrocarbon CH4 ("CH.sub.4")) with argon with (oxygen "O.sub.2"))	USPAT; US-PGPUB	2004/09/30 15:08
5	5450	(pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 15:12
6	1	((pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3) near10 dry) and ((hydrocarbon CH4 ("CH.sub.4")) and argon and oxygen "O.sub.2")	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 15:12
7	490	(hydrocarbon near3 gas) same (inert near3 gas) same (oxygen near3 gas)	USPAT; US-PGPUB	2004/09/30 15:14
8	22	((hydrocarbon near3 gas) same (inert near3 gas) same (oxygen near3 gas)) and ((pr photoresist photo?resist (photo near3 resist) resist) near10 (etch$3 pattern4 trim$4 remov$3))	USPAT; US-PGPUB	2004/09/30 15:15
-	325112	pr photoresist photo?resist (photo near3 resist) resist	USPAT; US-PGPUB	2004/06/21 14:56
-	43155	(pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))	USPAT; US-PGPUB	2004/06/21 14:56
-	44173	(pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))	USPAT; US-PGPUB	2004/06/21 14:57
-	53221	((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))	USPAT; US-PGPUB	2004/06/21 11:39
-	33206	(((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)	USPAT; US-PGPUB	2004/06/21 14:57
-	26375	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))	USPAT; US-PGPUB	2004/06/21 11:43

-	10795	(((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))	USPAT; US-PGPUB	2004/06/21 11:47
-	6173	((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow	USPAT; US-PGPUB	2004/06/21 11:45
-	6337	((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)	USPAT; US-PGPUB	2004/06/21 11:45
-	7436	((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure	USPAT; US-PGPUB	2004/06/21 11:46

| - | 3924 | ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure) | USPAT; US-PGPUB | 2004/06/21 11:46 |

| - | | 291 | (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:57 |

| | | 29 | (((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((C2H6 ("C.sub.2" adj3 "H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:58 |

| | | 44 | ((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((CHF3 ("CH" adj3 "F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:58 |

| | | 144 | (((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C" adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:58 |

| | | 95 | ((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3 "H.sub.3" adj3 "F")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:59 |

| - | | 11 | (((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((C2H2F4 ("C.sub.2" adj3 "H.sub.2" adj3 "F.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")) | USPAT; US-PGPUB | 2004/06/21 14:59 |

| - | 460 | ((((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (power watt)) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and pressure)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) ((((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and flow) and ((((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) ((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar"))))) and (etch$3 pattern4 trim$4)) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4))) and ((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4)) same ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 | USPAT; US-PGPUB | 2004/06/21 11:58 |

-	200756	pr photoresist photo?resist (photo near3 resist) resist	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:56
-	5332	(pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:56
-	4328	((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:57
-	2710	(((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:57
-	2	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:58
-	2	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((C2H6 ("C.sub.2" adj3 "H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:58
-	6	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CHF3 ("CH" adj3 "F.sub.3")("C" adj3 "H" adj3 "F.sub.3")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:58
-	2	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2")("C" adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:59
-	1	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH3F ("CH.sub.3" adj3 "F")("C" adj3 "H.sub.3" adj3 "F")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:59
-	0	((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((C2H2F4 ("C.sub.2" adj3 "H.sub.2" adj3 "F.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 14:59

-	9	(((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) (((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((C2H6 ("C.sub.2" adj3 "H.sub.6")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) (((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CHF3 ("CH" adj3 "F.sub.3") ("C" adj3 "H" adj3 "F.sub.3")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) (((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH2F2 ("CH.sub.2" adj3 "F.sub.2") ("C" adj3 "H.sub.2" adj3 "F.sub.2")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) (((((pr photoresist photo?resist (photo near3 resist) resist) and ((gas plasma) same (hydrocarbon oxygen inert))) and ((gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) (oxygen O2 "O.sub.2") (argon Ar "Ar")))) and (etch$3 pattern4 trim$4)) and ((CH3F ("CH.sub.3" adj3 "F") ("C" adj3 "H.sub.3" adj3 "F")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar")))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 15:00
-	325112	pr photoresist photo?resist (photo near3 resist) resist	USPAT; US-PGPUB	2004/06/21 16:43
-	11384	thin$4 near5 (pr photoresist photo?resist (photo near3 resist) resist)	USPAT; US-PGPUB	2004/06/21 15:53
-	20039	thin$4 with (pr photoresist photo?resist (photo near3 resist) resist)	USPAT; US-PGPUB	2004/06/21 15:53
-	10479	(thin$4 near5 (pr photoresist photo?resist (photo near3 resist) resist)) and (etch$3 trim$4 pattern$4)	USPAT; US-PGPUB	2004/06/21 15:54
-	1618	((thin$4 near5 (pr photoresist photo?resist (photo near3 resist) resist)) and (etch$3 trim$4 pattern$4)) and ((argon Ar) and (oxygen O2 "O.sub.2"))	USPAT; US-PGPUB	2004/06/21 16:07
-	337	(((thin$4 near5 (pr photoresist photo?resist (photo near3 resist) resist)) and (etch$3 trim$4 pattern$4)) and ((argon Ar) and (oxygen O2 "O.sub.2"))) and (CHF3 "CHF.sub.3" ("C" adj3 "H" adj3 "F.sub.3"))	USPAT; US-PGPUB	2004/06/21 15:56
-	405	(pr photoresist photo?resist (photo near3 resist) resist) and (micro near3 load$3)	USPAT; US-PGPUB	2004/06/21 16:06
-	105	((pr photoresist photo?resist (photo near3 resist) resist) and (micro near3 load$3)) and ((argon Ar) and (oxygen O2 "O.sub.2"))	USPAT; US-PGPUB	2004/06/21 16:43
-	200756	pr photoresist photo?resist (photo near3 resist) resist	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 16:43
-	517	(pr photoresist photo?resist (photo near3 resist) resist) and ((argon Ar) and (oxygen O2 "O.sub.2"))	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 16:43

-	3	((pr photoresist photo?resist (photo near3 resist) resist) and ((argon Ar) and (oxygen O2 "O.sub.2"))) and (micro near3 load$3)	EPO; JPO; DERWENT; IBM_TDB	2004/06/21 16:44
-	919	(pr photoresist photo?resist (photo near3 resist) resist) and (etch$3 pattern4 trim$4) and (gas plasma) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	USPAT; US-PGPUB	2004/09/30 14:31
-	63	((pr photoresist photo?resist (photo near3 resist) resist) and (etch$3 pattern4 trim$4) and (gas plasma) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))) and (critical near3 dimens$3)	USPAT; US-PGPUB	2004/09/30 14:36
-	39	((pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4) and (gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon) same (oxygen O2 "O.sub.2") same (argon Ar "Ar"))) and (critical near3 dimens$3)	USPAT; US-PGPUB	2004/09/30 14:20
-	3	(pr photoresist photo?resist (photo near3 resist) resist) and (etch$3 pattern4 trim$4) and (gas plasma) and ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4")) and (oxygen O2 "O.sub.2") and (argon Ar "Ar"))	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 14:37
-	81834	(CD (critical near3 dimens$3))	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 14:36
-	1637	((CD (critical near3 dimens$3))) and (pr photoresist photo?resist (photo near3 resist) resist)	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 14:37
-	769	(((CD (critical near3 dimens$3))) and (pr photoresist photo?resist (photo near3 resist) resist)) and (pattern$4 etch$3 trim$4)	EPO; JPO; DERWENT; IBM_TDB	2004/09/30 14:41
-	304	(pr photoresist photo?resist (photo near3 resist) resist) same (etch$3 pattern4 trim$4) and (gas plasma) same ((CH4 "CH.sub.4" ("C" adj3 "H.sub.4") hydrocarbon) same (oxygen O2 "O.sub.2") same (argon Ar "Ar"))	USPAT; US-PGPUB	2004/09/30 14:43